

CLAIMS

1. A method for manufacturing a plasma display panel (PDP) including a process for forming a metal oxide film onto a substrate of the PDP, the method comprising:

5 forming the metal oxide film within a range of 1×10^{-1} Pa to 1×10^{-2} Pa in a degree of vacuum in a deposition room.

2. The method for manufacturing the PDP of claim 1,
 wherein the degree of vacuum is controlled by introducing oxygen gas
10 while the deposition room is exhausted.

3. The method for manufacturing the PDP of claim 1,
 wherein the degree of vacuum is controlled by introducing at least one gas selected from the group consisting of water, hydrogen, carbon monoxide and
15 carbon dioxide while the deposition room is exhausted.

4. The method for manufacturing the PDP of claim 1,
 wherein the degree of vacuum is controlled by introducing inert gas while the deposition room is exhausted.

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5. The method for manufacturing the PDP of claim 1,
 wherein the degree of vacuum is controlled by introducing oxygen gas and at least one of inert gas and carbon dioxide while the deposition room is exhausted.

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